

amendment in accordance with 37 C.F.R. § 1.121(c)(1)(ii). Any claim not accompanied by a marked-up version has not been changed relative to the immediate prior version, except that marked-up versions are not being supplied for any added claim or canceled claim.

CLAIMS

Cancel claims ~~42-44~~.

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53. (Amended) A physical vapor deposition target comprising an alloy of copper and one or more other elements, the one or more other elements being present in the alloy at a total concentration from less than 1.0 at% to 0.001 at% and being selected from the group consisting of Mo, Tc, Re, and Ti.

54. The physical vapor deposition target of claim 53 wherein the one or more other elements are present in the alloy at a total concentration at from 0.005 at% to 0.1 at%.

55. The physical vapor deposition target of claim 53 comprising an RF sputtering coil.

60. (New) The physical vapor deposition target of claim 53 wherein the element comprises Mo.

61. (New) The physical vapor deposition target of claim 53 wherein the element comprises Tc.

62. (New) The physical vapor deposition target of claim 53 wherein the element comprises Re.

63. (New) The physical vapor deposition target of claim 53 wherein the element comprises Ti.